

Economic growth of vertically aligned multiwalled carbon nanotubes in nitrogen atmosphere

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ABSTRACT

Vertically aligned carbon nanotube (VACNT) arrays are widely studied because of their immense potential in a wide range of applications. In order to tailor the properties of carbon nanotubes (CNTs) for a particular application, vertical alignment in the form of sheet is a major breakthrough. Herein we report an economic and effective strategy developed to synthesise aligned multiwalled carbon nanotube sheets using Al powder as buffer layer. We achieved easy growth of VACNTs sheets using toluene/ferrocene solution in a two-zone furnace by chemical vapor deposition method. First zone was set at temperature 200 °C and other zone was set at temperature 750 °C for the synthesis of VACNTs. Almost 500 µm long VACNT sheet was grown. We observed the significant growth of VACNT sheet on Al powdered quartz substrate in nitrogen medium. Uniform length of CNTs was maintained all over the sheet and additionally nitrogen is an economical alternative rather than other inert gases. Copyright © 2015 VBRI Press.

Keywords: Chemical vapor deposition; vertically aligned CNT; buffer layer; synthesis.

Introduction

In early 1950's tubular carbon filaments were produced by two Russian scientists Radushkevich and Lykynovich [1]. Potential of carbon nanotubes (CNTs) was felt tremendous after the work of Iijima *et al.* [2] and Bethune in 1993 [3]. CNTs have marvellous electrical [4, 5], thermal [6], optical [7], hydrophobic [8] and mechanical[9] properties. Almost every field of technology like Biomedical [10], Electronic [5], Bio Sensors [11,12], super-capacitors [13], Industrial area[14, 15] etc. have applied these properties e.g. replacing copper in interconnected circuits with CNTs. The advantage of CNTs is that they can be grown in high aspect ratio.

Various methods have been discovered to synthesise CNTs but chemical vapor deposition (CVD) [16] method is the most economic and effective method because of better control over parameters like precursor flow rate, composition, temperature, catalyst [17]. CVD method can be used for both liquid and gaseous precursors. Aligned CNT arrays provide more advanced properties rather than random oriented CNT powder. Mechanical properties [18] can be increased by using aligned CNTs. Well aligned CNT arrays have been synthesized by chemical vapor deposition method [19, 20]. In CVD method precursor flows along with carrier gases like hydrogen or argon into the reactor. The reactor is heated over 660 °C - 800 °C and at that point solution decomposes and forms CNTs in the presence of

catalyst or structure directing matrix. Water assisted growth of CNTs has been reported by Shenghua *et al.* [21-23]. The catalyst is deposited on the substrate and the substrate is placed inside the reactor and at 750 °C hydrocarbon solution is flown. Floating catalyst method is also used to synthesise vertically aligned carbon nano tubes (VACNTs). In floating catalyst method, carbon and catalyst source are mixed together and flown into the reactor. Carrier gases like hydrogen [24, 25] argon [26, 27] are generally used as reported earlier. Much work has been done on the deposition of catalyst and buffer layer on the substrate [28]. Buffer layer [29] is also an important parameter for preventing agglomeration of catalyst into substrate. Qingwen [30] *et al.* reported a dense Al₂O₃ buffer layer (10 nm) deposited on a Si substrate using ion-beam assisted deposition (IBAD), and a Fe film (1 nm) was deposited on the buffer layer. Xuemei [31] and Yang [32] *et al.* reported deposition of buffer layer and catalyst layer by electron beam evaporation and also used Ar and H₂ as carrier gases. Predisposition methods like e-beam [33, 34], sputtering [35], thermal deposition are used to prepare buffer layer and catalyst layer on substrate. These methods are expensive and mostly not feasible and a very few researchers have worked to solve these issues.

Here, we present a better economic technique to produce VACNTs by using aluminium powder as buffer layer and nitrogen as the carrier gas at 750 °C. We successfully synthesized VACNTs of high quality by CVD

thickness of the films was determined from edge-on SEM images of cleaved samples. **Fig. 4(a)** shows a typical image of almost half millimetre (500 μm) grown VACNTs and **Fig. 4(b)** and (c) show the high magnification images of aligned nanotubes. **Fig. 4(b)** shows the bundled pillars of aligned tubes and **Fig. 4(c)** shows the densely grown MWCNTs. Further characterization was done using RAMAN, XRD, and TEM for in depth studies.

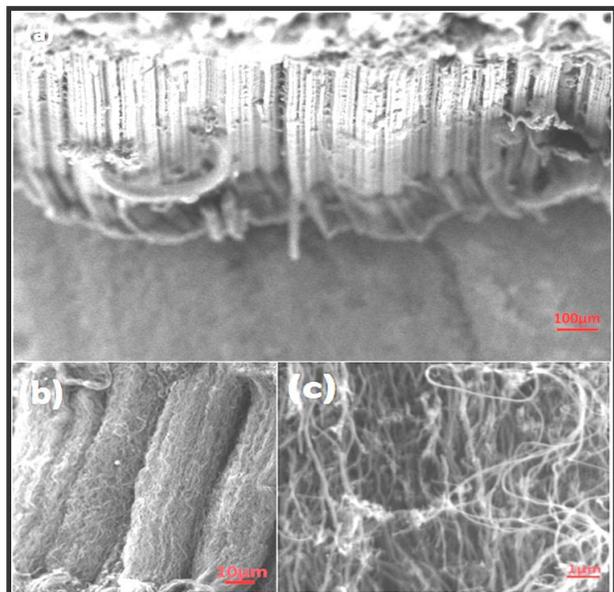


Fig. 4. Various SEM image of the as grown VACNTs.

Fig. 5 depicts the Raman spectrum of the side walls of the VACNTs. The expected D and G bands are obtained at 1350 and 1574 cm^{-1} , respectively. Ratio of intensity of D band (I_D) and G band (I_G) gives the quality factor which is obtained as 0.85 thereby confirming the synthesis of good quality CNT.

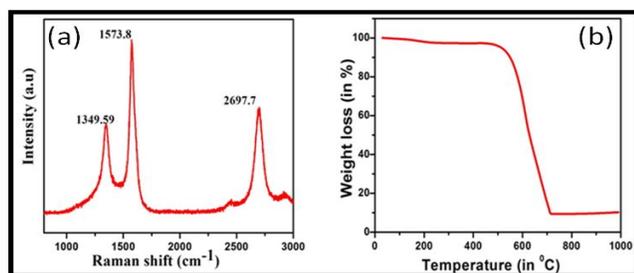


Fig. 5. (a) Raman spectrum of MWCNTs and (b) TGA curve of MWCNTs.

Thermo gravimetric analysis (TGA) was done to study the weight loss with increase in temperature. Sample was heated from 30 $^{\circ}\text{C}$ to 1000 $^{\circ}\text{C}$ in the air and the residual mass was studied. The result showed that only 9.4 % of catalyst was left behind, which proves good purity of the MWCNTs.

Structural and compositional studies were performed by using XRD. It is a non-destructive technique which reveals information about crystallographic structure, chemical composition and physical properties of the material. XRD pattern of VACNT is shown in **Fig. 6** in which, a sharp

peak determined at 2θ value of 25.8° is obtained which corresponds to the (0 0 2) planes of graphitic structure. Due to (1 1 0) and (1 0 0) graphitic planes humps in around 43° are obtained confirming the successful growth of CNTs.

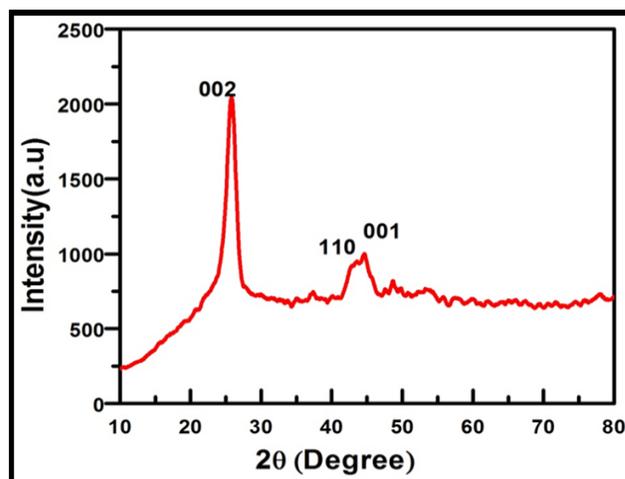


Fig. 6. XRD image of nitrogen grown VACNTs.

In order to carry out fine structural analysis of the as obtained CNTs, TEM images were thoroughly studied. **Fig. 7(a)** show the varied diameter CNTs as peeled out from the substrate. Similarly **Fig. 7(b)** shows the HRTEM image of very few-walled CNTs where number of walls obtained is three as calculated and **Fig. 7(c)** shows the HRTEM image of multi walled CNTs with 15 walls. Small amount of catalyst particles encapsulated within the walls of the MWCNTs are also portrayed as visible in **Fig. 7(a)**.

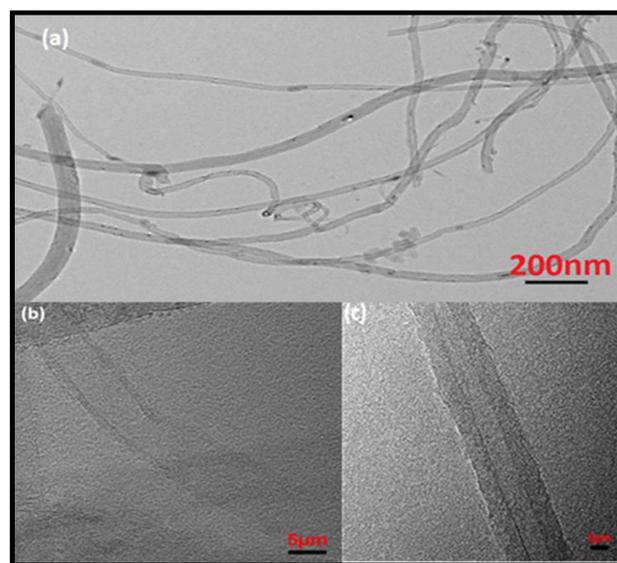


Fig. 7. (a) TEM images of the MWCNTs (b) and (c) HRTEM images of the MWCNTs.

Hence from the various TEM images it was confirmed that clean and good quality of graphitic layers were observed in the walls of the VACNTs grown. These various characterizations confirmed the successful growth of VACNT sheets in a much economical methodology. We intend to grow these sheets commercially and further

investigate the mechanism for length-dependent parameters of the growth of VACNT sheets.

Conclusion

VACNT sheets were successfully synthesized by CVD method using a two-zone furnace using nitrogen as the carrier gas. Etching of the substrate creates pores and Al powder used as buffer layer on the quartz substrate is soaked into these pores that results in the alignment of the CNTs. Use of Al powder prevents agglomeration of catalyst on the substrate. Factors like choice of the carrier gas, buffer layer, and catalyst contributed to the sustained and efficient growth of VACNT sheets. This report presents the novel economic method to synthesise VACNTs that is way more efficient than the other costlier alternative techniques like e-beam evaporation, sputtering. VACNTs of 500 μ m in length were achieved which were spread throughout the sheet, grown at temperature 750°C with good alignment. This structural feature allows for processing tailored VACNT sheets for a variety of applications.

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